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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

William N. Partlo, et al.

Serial No.: 10/798,740

Filing Date: March 10, 2004

Title: COLLECTOR FOR EUV LIGHT
SOURCE

Examiner: Unassigned

Group Art Unit: Unassigned

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with 37 C.F.R. § 1.97 and § 1.98, applicants submit for consideration in the above-identified application the attached Form PTO-1449. The Information Disclosure Statement submitted herewith is being filed before the mailing date of the first Office Action on the merits. Copies of the cited references are not provided pursuant to the USPTO waiving the requirement of submitting patent copies for applications filed after June 30, 2003, however Items AL through BS are provided herewith.

It is respectfully requested that the Examiner indicate consideration of the cited references by returning a copy of the attached form PTO-1449 with initials or other appropriate marks.

This Information Disclosure Statement under 37 C.F.R. § 1.97 is not to be construed as a representation that: (i) a complete search has been made; (ii) additional information material to the examination of this application does not exist; (iii) the information, protocols, results and the like reported by third parties are accurate or enabling; or (iv) the above information constitutes prior art to the subject invention.

Accordingly, no fee is believed to be due. The Commissioner is hereby authorized to charge any fees, or to credit any overpayment to Deposit Account No. 03-40607

Respectfully submitted,



William Cray; Reg. No. 27,627

May 6, 2004
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| U.S. Department of Commerce, Patent and Trademark Office | | | | | Atty Docket No. | | Serial No. | |
| | | | | | 2003-0083-01 | | 10/798,740 | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | | Applicant(s) | | | |
| (Use several sheets if necessary) | | | | | William N. Partlo, et al. | | | |
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